2018년 2월 6일(화), 14:10-15:55
Room K (육백II, 6층)

Q. Metrology, Inspection, and Yield Enhancement 분과
[TK2-Q] Nanoanalysis

TK2-Q-1 **14:10-14:25**	**Dynamic Thin Film Thickness Measurement based on Snapshot Spectro-Ellipsometry** Vamara Dembele[1], Inho Choi[1], Madhan Jayakumar Paul[1], Sukhyun Choi[1], Junho Kim[1], Won Chegal[2], and Daesuk Kim[1] *[1]Division of Mechanical System Engineering, Chonbuk National University, [2]Advanced Instrumentation Institute, Korea Research Institute of Standards & Science*
TK2-Q-2 **14:25-14:55**	**[초청]** **미정** 고대홍 *연세대학교*
TK2-Q-3 **14:55-15:25**	**[초청]** **Applications of TEM Electron Energy-Loss Spectroscopy (EELS) Analysis for Materials in Semiconductor Devices** Jucheol Park, Jeong Eun Chae, Ji-Soo Kim, SangYeol Nam, and Min-Soo Kim *Materials Characterization Center, Gumi Electronics & Information Technology (GERI)*
TK2-Q-4 **15:25-15:40**	**Wafer 표면 Roughness에 따른 Thermal Oxide 영향 연구** 정성우, 박정길, 김자영, 강희복 *SK Siltron*
TK2-Q-5 **15:40-15:55**	**Detection of Metal Contamination in the Layer of Silicon Wafers** Seung-Ik Jo, Ji-Yeon Lim, Sung-wook Lee *SK Siltron*